



DFT Calculations Pursuant to Modeling Atomic Displacement Damage in Circuits

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September 13, 2010**

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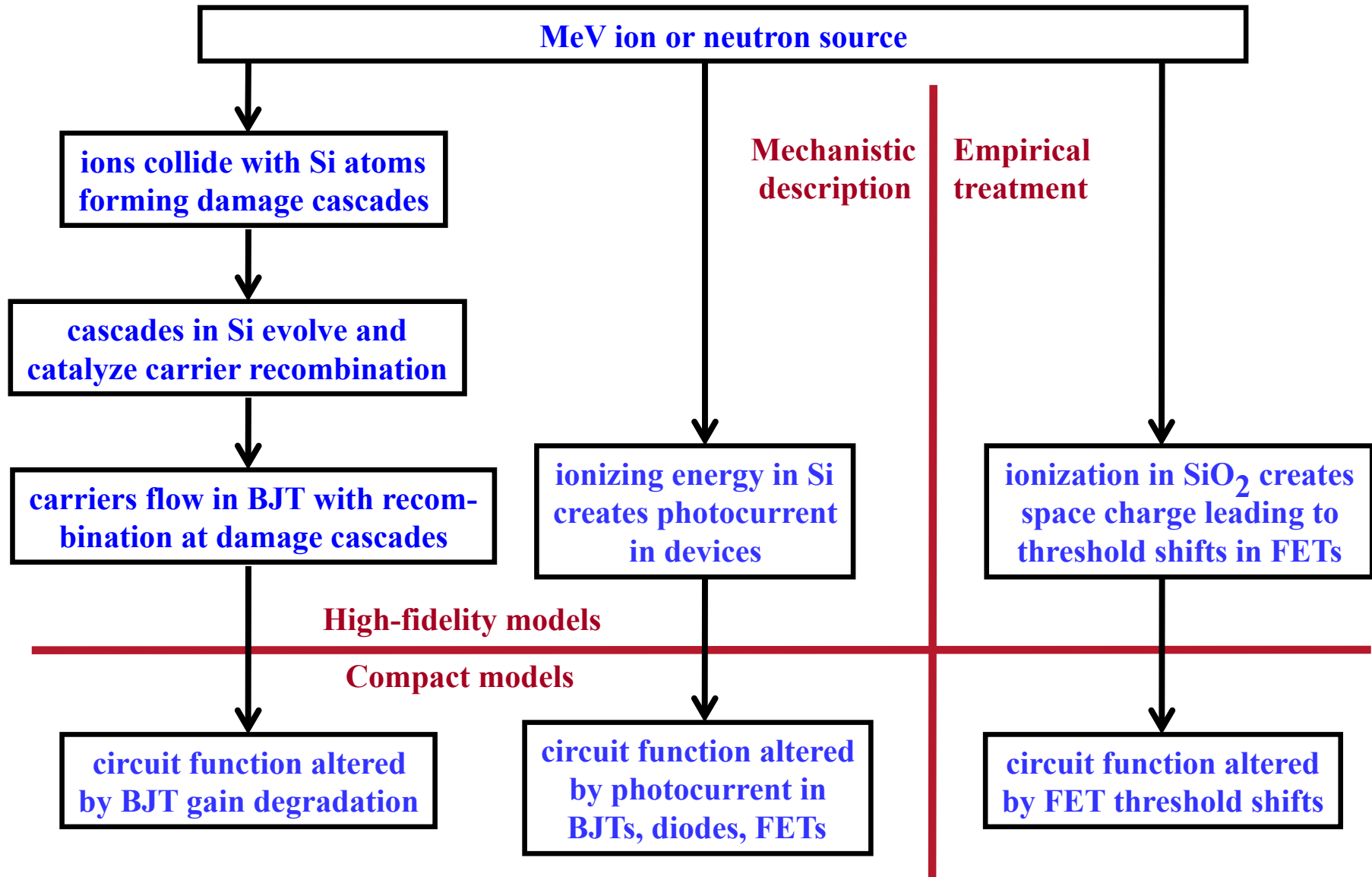


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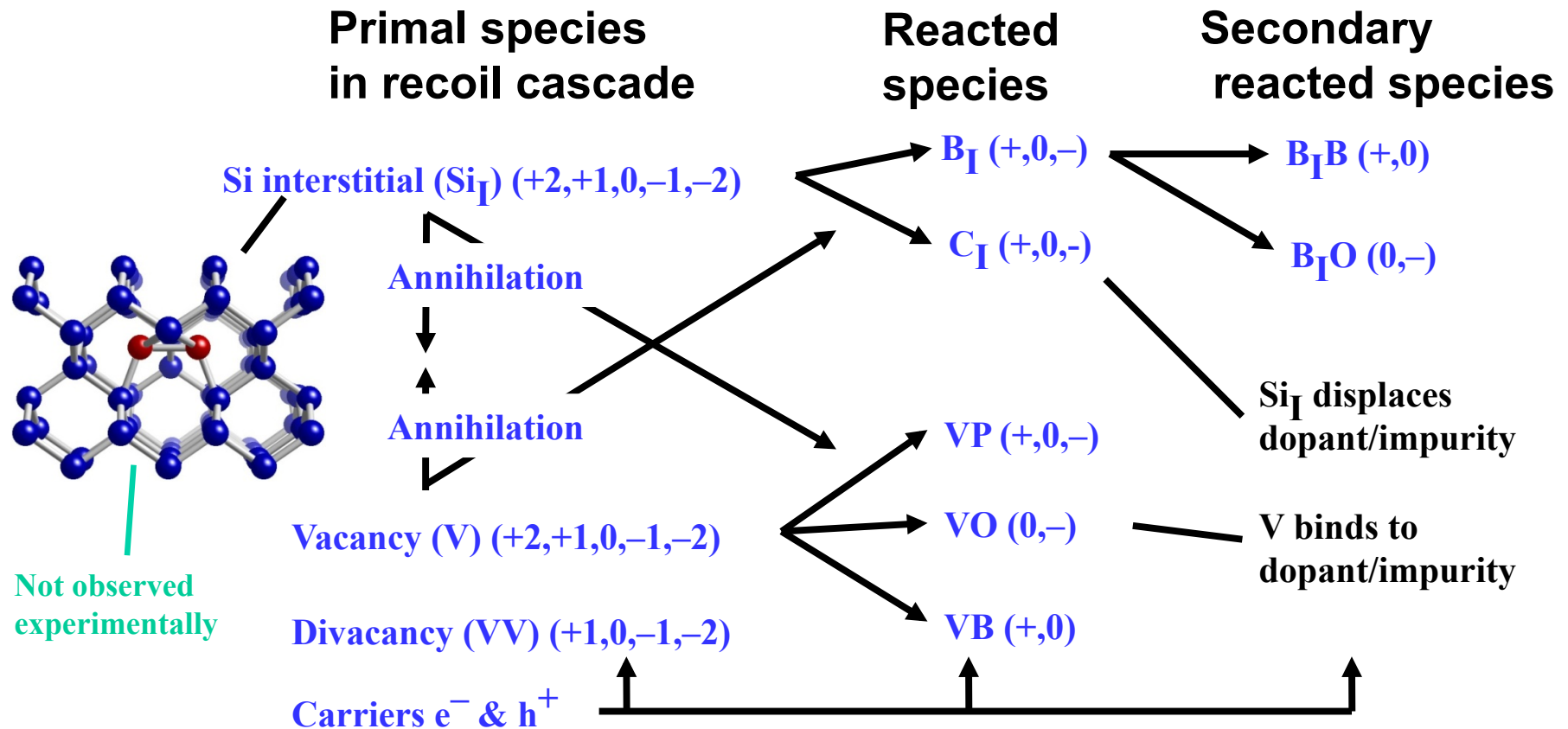


Relevant phenomena for Si devices





Defect and carrier reactions in atomistic model



- Assessment of relevant defects and associated physical parameters based on literature.
- Knowledge gaps addressed using density-functional-theory (DFT).
- Final parameter refinement using model-development irradiation experiments.

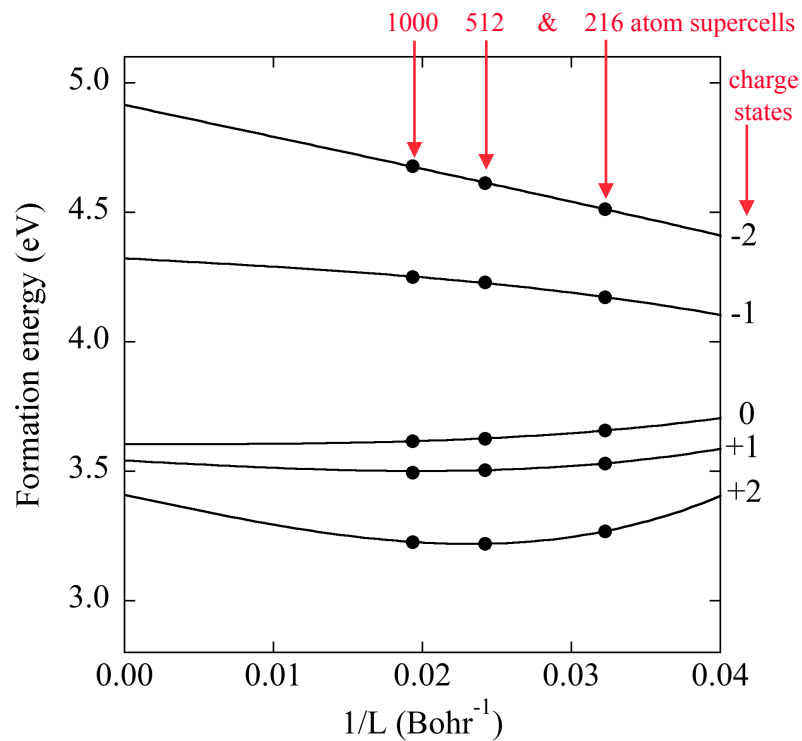


DFT results for the Si vacancy

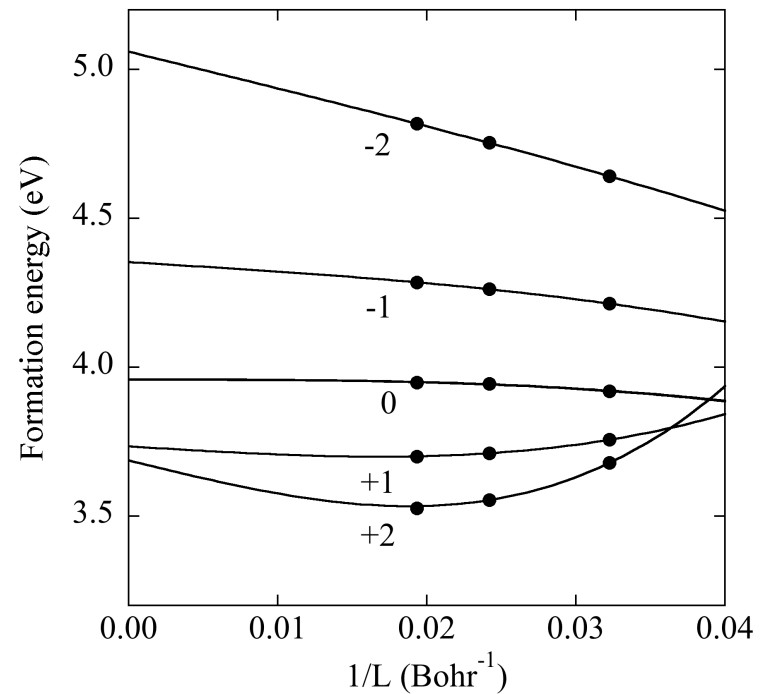
Supercell-size effects addressed by computing formation energies in 216-, 512-, and 1000-atom supercells and fitting to the Makov-Payne expression:

$$E^f[V_{\text{Si}}^q; L] = E^f[V_{\text{Si}}^q; L \rightarrow \infty] - \frac{2.8373q^2}{\epsilon L} + \frac{A_3}{L^3}$$

Ground states



Saddle points



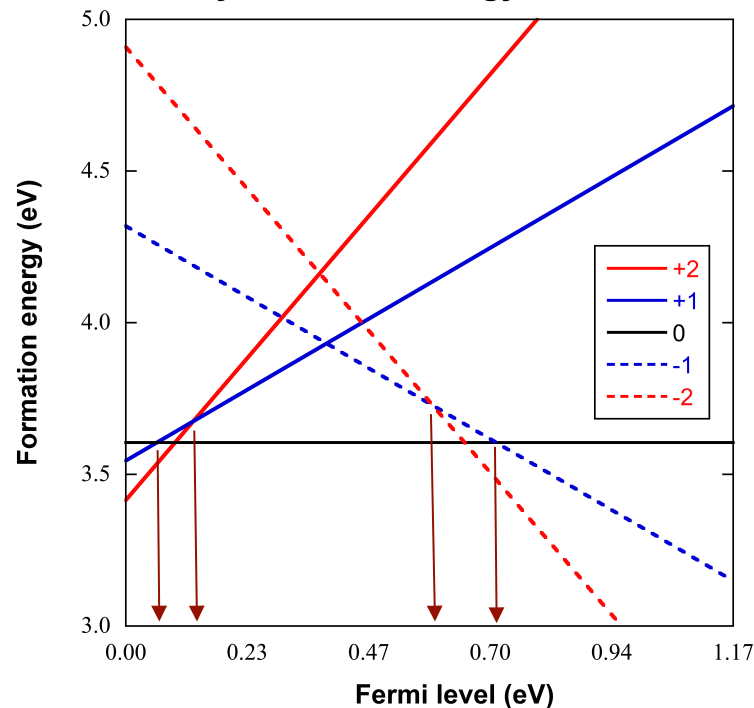


Extracting energy levels and diffusion activation energies

Energy levels are the crossing points in plots of the ground-state formation energies versus Fermi level for charge states differing by 1

$$E^f[V_{\text{Si}}^q; E_F] = E^f[V_{\text{Si}}^q; L \rightarrow \infty] + qE_F$$

Vacancy formation energy vs. Fermi level

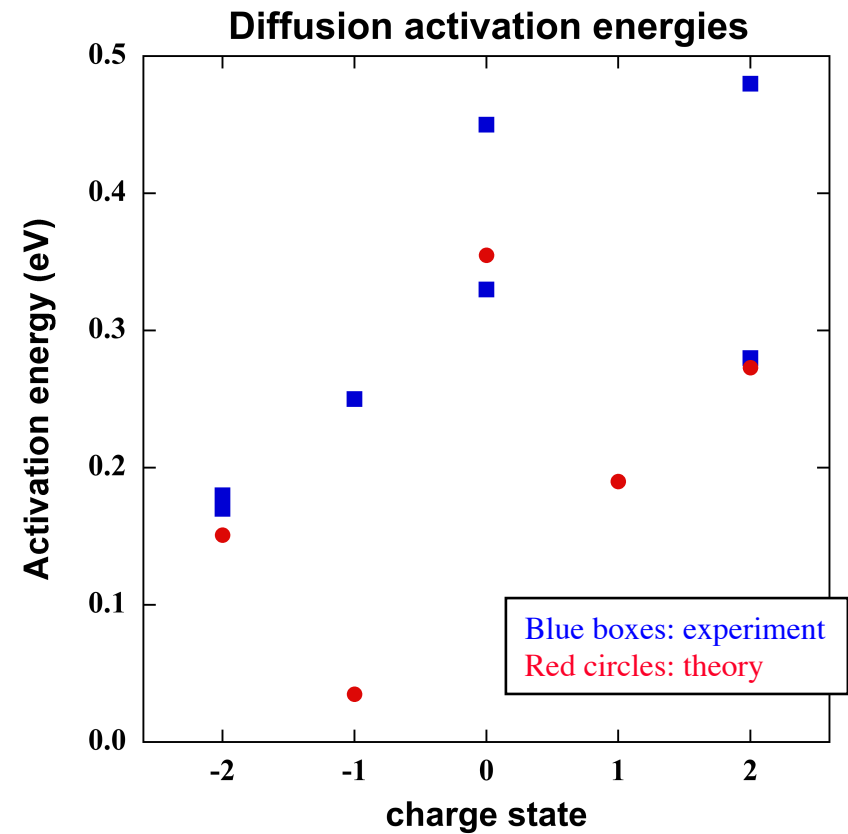
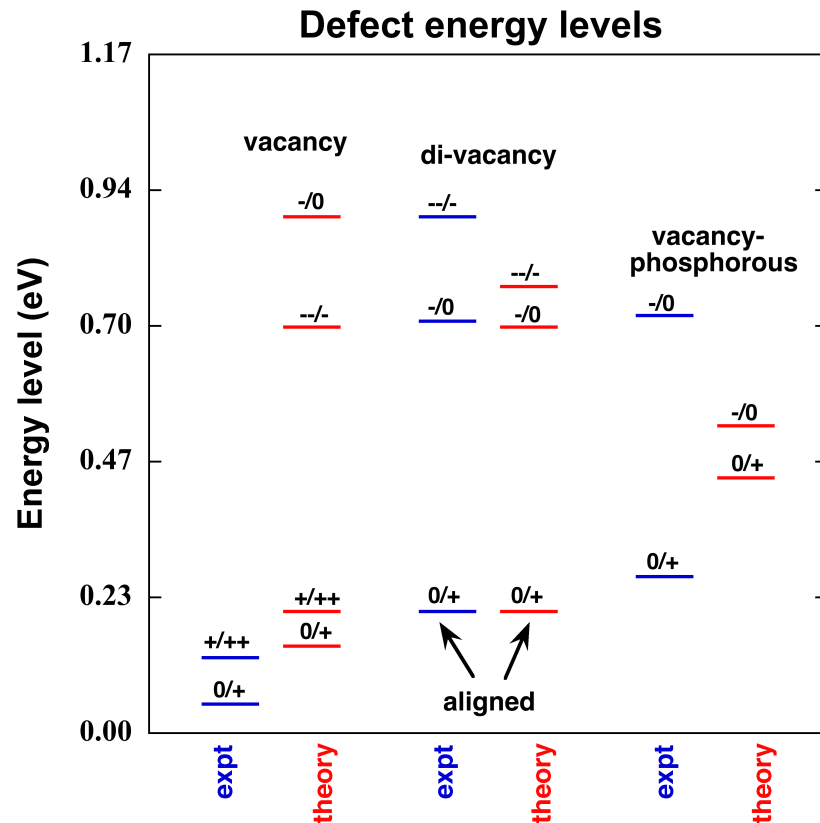


Diffusion activation energies are the differences in the extrapolated saddle-point (SP) and ground state (GS) formation energies

$$E^A[V_{\text{Si}}^q] = E^f[V_{\text{Si}}^q; \text{SP}; L \rightarrow \infty] - E^f[V_{\text{Si}}^q; \text{GS}; L \rightarrow \infty]$$



Comparison with experiments



[Phys. Rev. B 74, 165116 (2006)] for vacancy results
 [Phys. Rev. B 74, 205208 (2006)] for divacancy results
 [J. Appl. Phys. 103, 083517 (2008)] for vacancy diffusion results

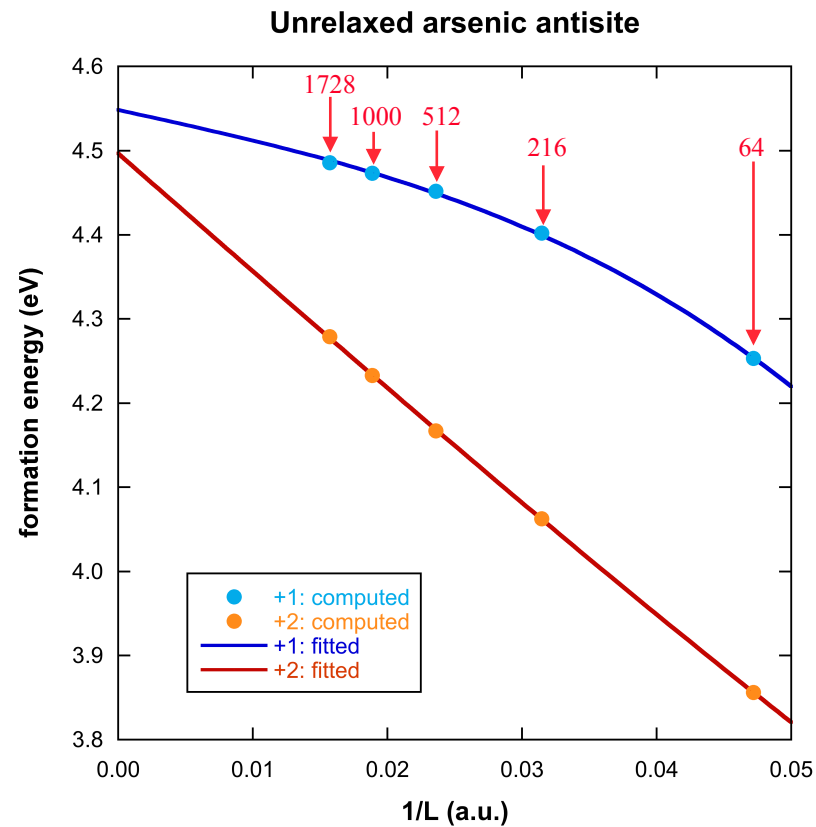


Atomic displacement damage in GaAs

- Current work is focusing on defects in GaAs
- The need for DFT results for GaAs is more urgent because less is known about defects in GaAs than defects in Si
- Also, DLTS is unlikely to shed light on the energy levels or populations of individual defects following MeV ion irradiation



An aside: estimating a value for ϵ of GaAs



The fits were constrained to use the same value of ϵ yielding 11.0.

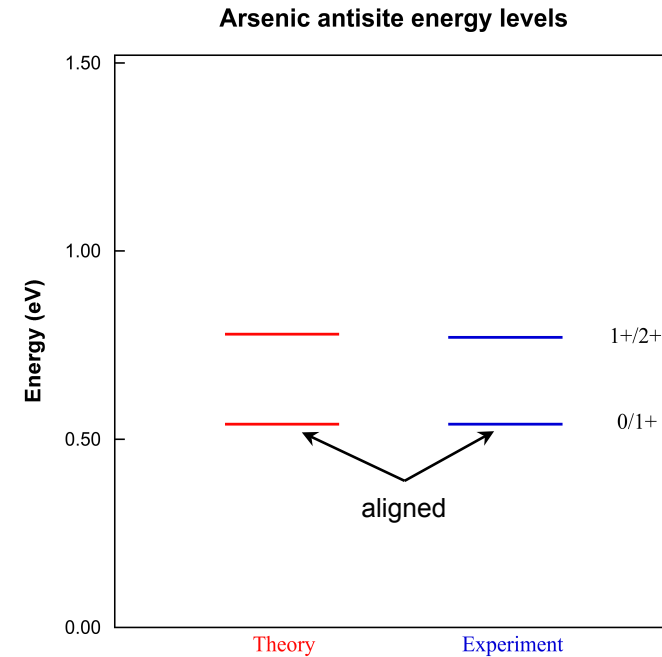
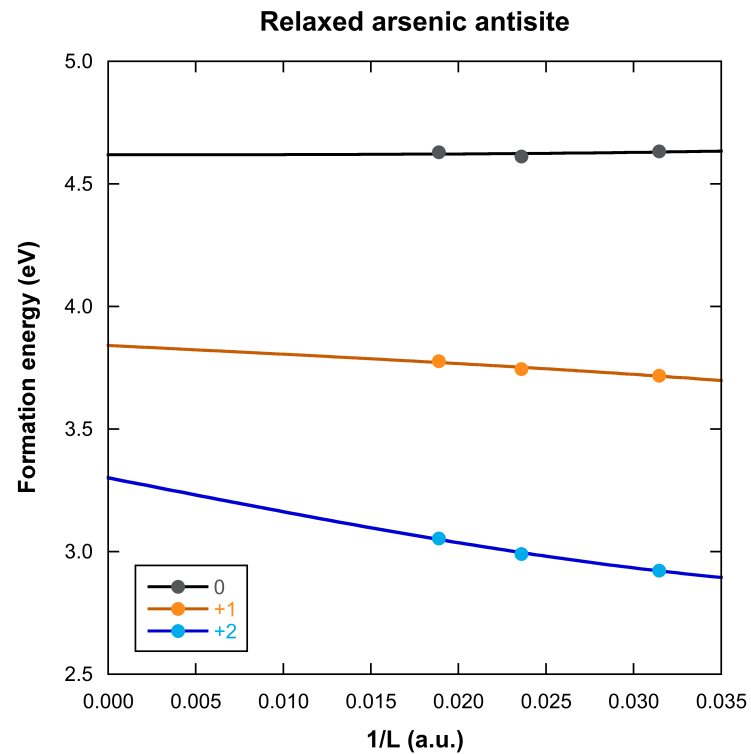
Published values are:

DFT: 10.9 – 14.4

Experiment: 10.6, 10.9



Results for the relaxed arsenic antisite

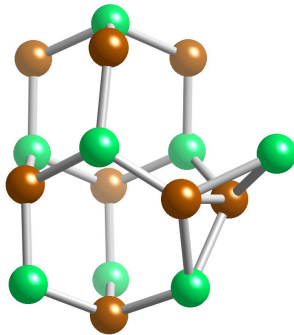


A shift was computed by aligning the computed 0/1+ level with the measured 0/1+ value. The computed 1+/2+ level then differs from the measured 1+/2+ level by 10 meV.

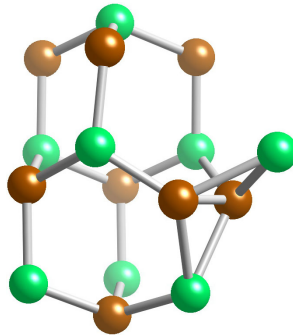


DFT results for the As interstitial in GaAs

[110] Split Interstitial : C_{2v} symmetry

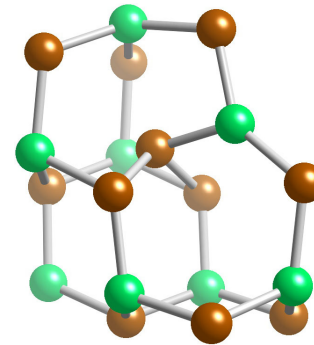


-1 charge state



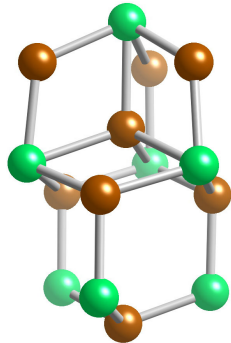
0 charge state

Bridging : C_{1h} symmetry

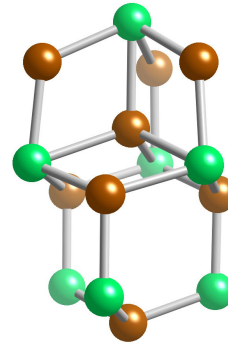


+1 charge state

Tetrahedral : T_d symmetry



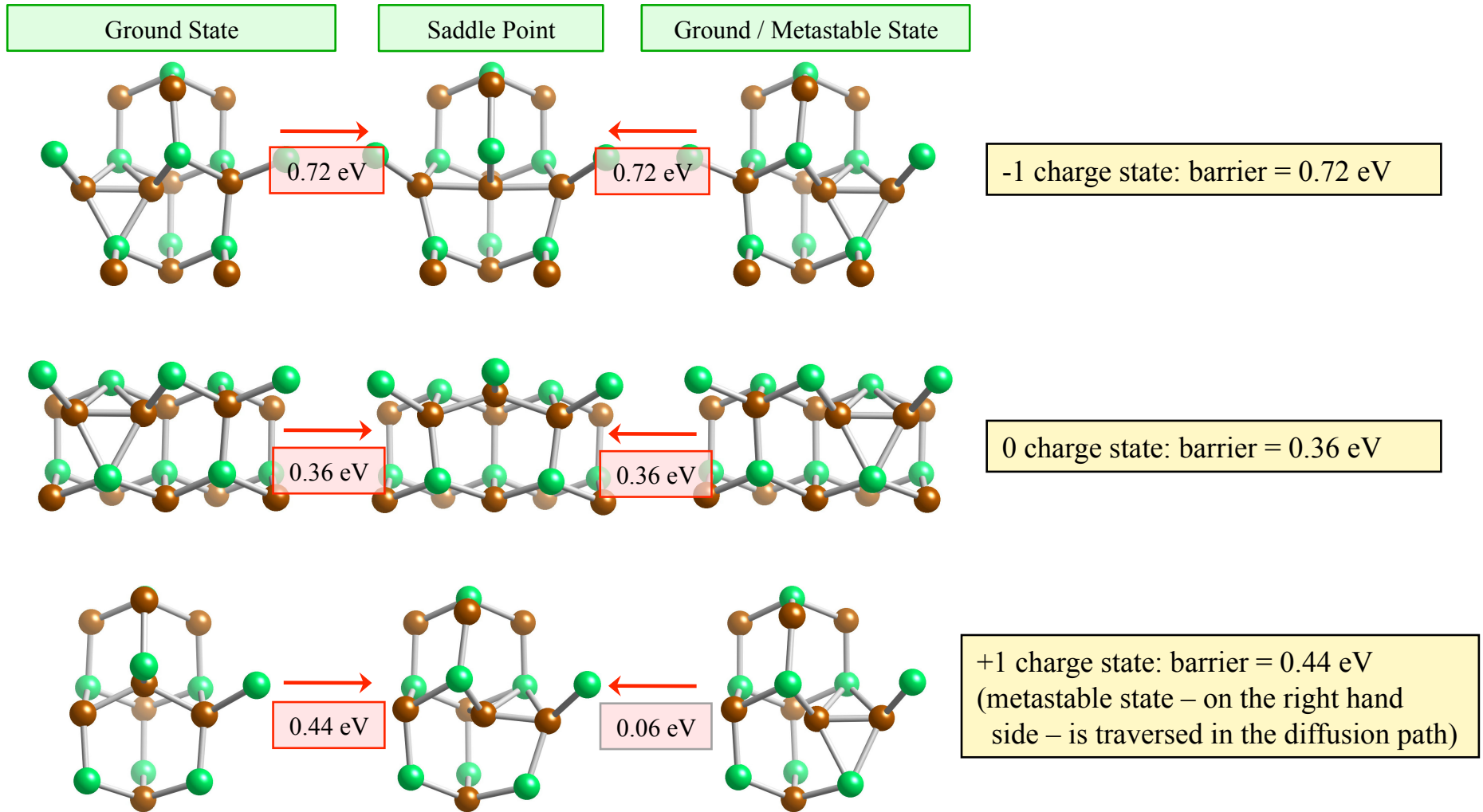
+2 charge state



+3 charge state

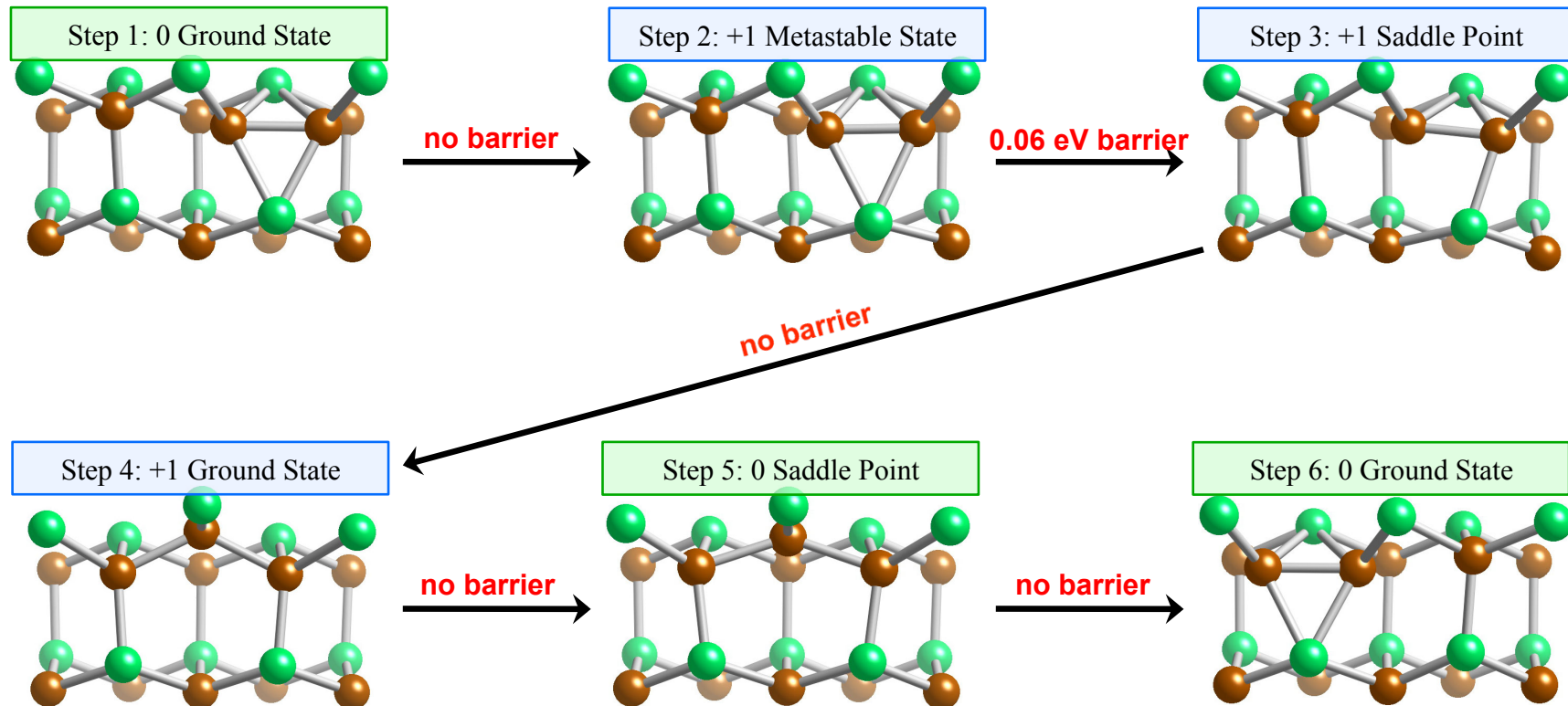


As₁ thermal diffusion pathways





Carrier assisted diffusion





Summary

- Sandia is undertaking to develop a multiscale model of atomic displacement damage in Si and GaAs-based circuits
- DFT is being used to provide information about defect properties when these are not available from experiments
- Current state-of-the-art DFT energy levels appear to differ from measured values by 0.1 – 0.2 eV
- Additional activities:
 - The same protocols are being applied to the Ga vacancy in GaN
 - We are exploring the use of exact exchange via an optimized effective potential



Supplementary material: Treating charged defects in DFT calculations

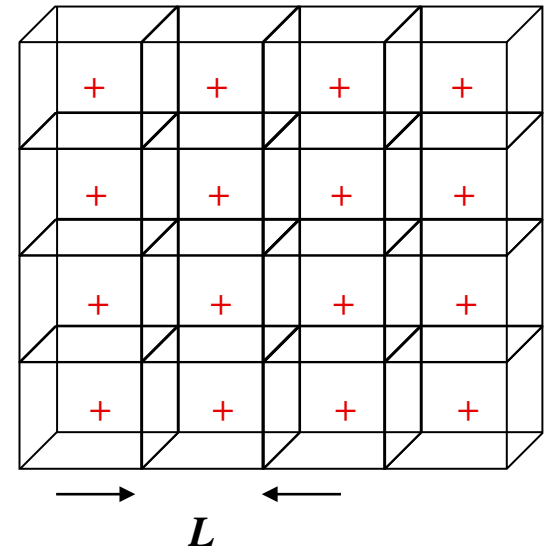
A significant challenge is treating the long-ranged electrostatic potentials arising from charged defects when using supercells and periodic boundary conditions

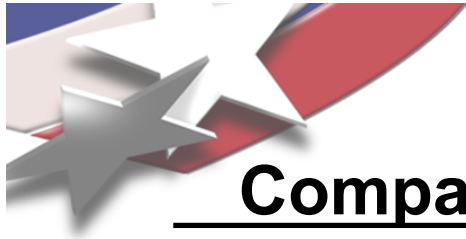
We have considered two methods for doing this:

- 1) uniform background charge (UBC) method
- 2) local-moment counter charge (LMCC) method

UBC Method: Introduce a uniform charge distribution to nullify the long-ranged electrostatic interactions

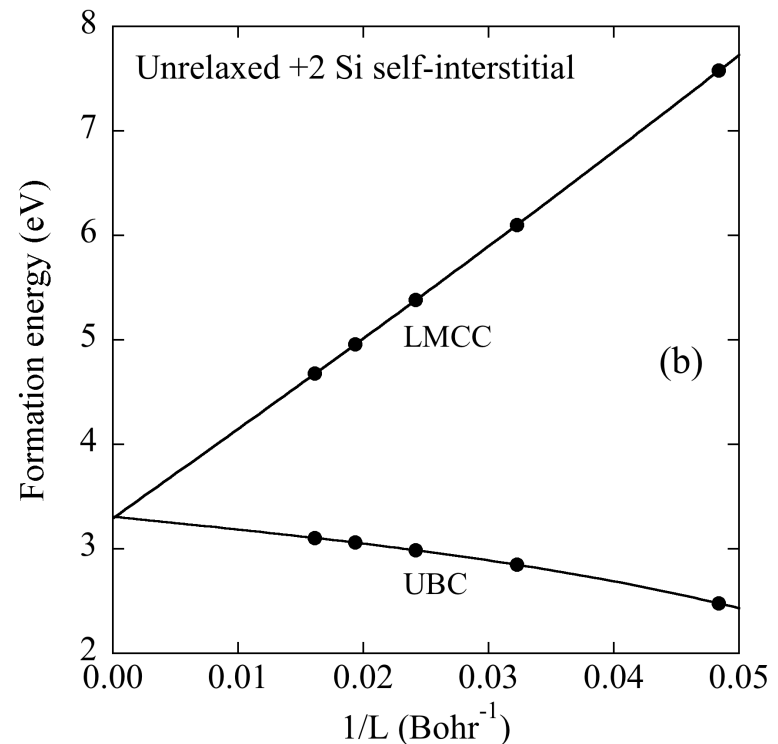
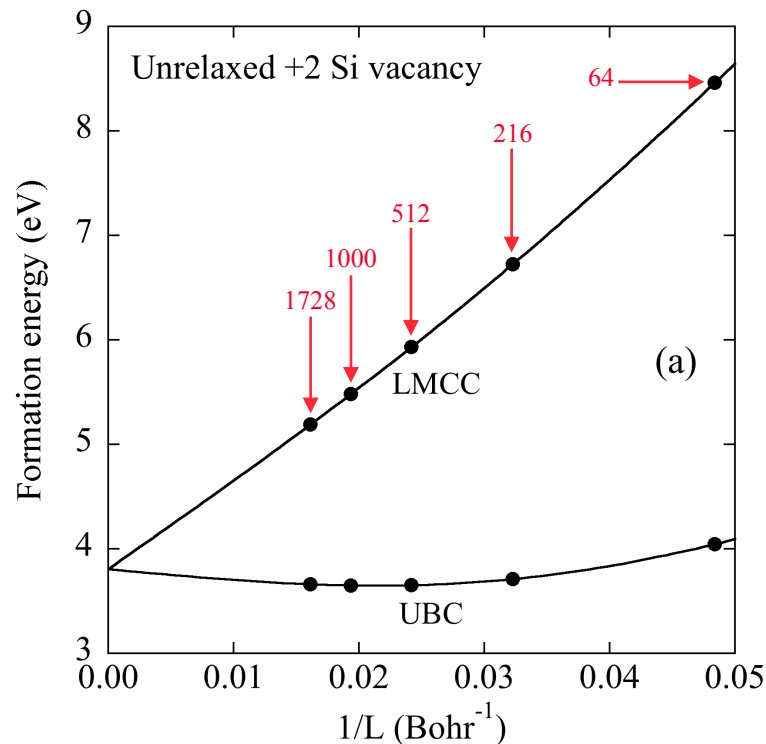
LMCC Method: Introduce a gaussian counter charge at the defect site that produces the correct electrostatic potential up to the cell boundary





Supplementary material: Comparison of the UBC and LMCC methods

- It can be shown analytically that both methods give the same formation energy as L goes to infinity [Phys. Rev. B 74, 235209 (2006)]
- This is illustrated below where results obtained in 64-, 216-, 512-, 1000-, and 1728-atom supercells are fit to the expression $E^f(L) = E^f(L \rightarrow \infty) + \frac{A_1}{L} + \frac{A_3}{L^3} + \frac{A_5}{L^5}$





Supplementary material: Are analytic corrections viable?

- In the UBC method, a simple expression is available for the linear

$$E_1 = -\frac{2.8373q^2}{\varepsilon L}$$

dependence where q is the charge and ε is the dielectric constant

- In the LMCC method, an approximate expression for the polarization

$$E_p = -\left(1 - \frac{1}{\varepsilon}\right) \frac{q^2}{(R_{Jost} - \beta)} ; R_{Jost} = L / \left[\frac{4\pi}{3} \right]^{\frac{1}{3}}$$

energy of the surrounding bulk material can be added to the formation where β is an empirical parameter usually taken to be 0.8 a.u.

- Our tests indicate that these corrections are not adequate for our purposes